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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/671,478	09/27/2000	KOUCHIROU WAKABAYASHI	107454	7122

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EXAMINER

PSITOS, ARISTOTELIS M

ART UNIT	PAPER NUMBER
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2653

DATE MAILED: 01/06/2004

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Please find below and/or attached an Office communication concerning this application or proceeding.

Advisory Action

Application No.

09/671,478

Applicant(s)

WAKABAYASHI ET AL.

Examiner

Aristotelis M Psitos

Art Unit

2653

-The MAILING DATE of this communication appears on the cover sheet with the correspondence address -

THE REPLY FILED 17 December 2003 FAILS TO PLACE THIS APPLICATION IN CONDITION FOR ALLOWANCE. Therefore, further action by the applicant is required to avoid abandonment of this application. A proper reply to a final rejection under 37 CFR 1.113 may only be either: (1) a timely filed amendment which places the application in condition for allowance; (2) a timely filed Notice of Appeal (with appeal fee); or (3) a timely filed Request for Continued Examination (RCE) in compliance with 37 CFR 1.114.

PERIOD FOR REPLY [check either a) or b)]

- a) ☒ The period for reply expires 4 months from the mailing date of the final rejection.
- b) ☐ The period for reply expires on: (1) the mailing date of this Advisory Action, or (2) the date set forth in the final rejection, whichever is later. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of the final rejection. **ONLY CHECK THIS BOX WHEN THE FIRST REPLY WAS FILED WITHIN TWO MONTHS OF THE FINAL REJECTION. See MPEP 706.07(f).**

Extensions of time may be obtained under 37 CFR 1.136(a). The date on which the petition under 37 CFR 1.136(a) and the appropriate extension fee have been filed is the date for purposes of determining the period of extension and the corresponding amount of the fee. The appropriate extension fee under 37 CFR 1.17(a) is calculated from: (1) the expiration date of the shortened statutory period for reply originally set in the final Office action; or (2) as set forth in (b) above, if checked. Any reply received by the Office later than three months after the mailing date of the final rejection, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

1. ☐ A Notice of Appeal was filed on _____. Appellant's Brief must be filed within the period set forth in 37 CFR 1.192(a), or any extension thereof (37 CFR 1.191(d)), to avoid dismissal of the appeal.
2. ☐ The proposed amendment(s) will not be entered because:
- (a) ☐ they raise new issues that would require further consideration and/or search (see NOTE below);
 - (b) ☐ they raise the issue of new matter (see Note below);
 - (c) ☐ they are not deemed to place the application in better form for appeal by materially reducing or simplifying the issues for appeal; and/or
 - (d) ☐ they present additional claims without canceling a corresponding number of finally rejected claims.

NOTE: _____

3. ☒ Applicant's reply has overcome the following rejection(s): as 1-5 cancelled
4. ☐ Newly proposed or amended claim(s) _____ would be allowable if submitted in a separate, timely filed amendment canceling the non-allowable claim(s).
5. ☒ The a) ☐ affidavit, b) ☐ exhibit, or c) ☒ request for reconsideration has been considered but does NOT place the application in condition for allowance because: See Continuation Sheet.
6. ☐ The affidavit or exhibit will NOT be considered because it is not directed SOLELY to issues which were newly raised by the Examiner in the final rejection.
7. ☒ For purposes of Appeal, the proposed amendment(s) a) ☐ will not be entered or b) ☒ will be entered and an explanation of how the new or amended claims would be rejected is provided below or appended.

The status of the claim(s) is (or will be) as follows:

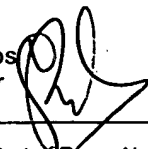
Claim(s) allowed: _____

Claim(s) objected to: _____

Claim(s) rejected: 6-20.Claim(s) withdrawn from consideration: It is noted that the amendment after final cancels claims 1-5.

8. ☐ The drawing correction filed on _____ is a) ☐ approved or b) ☐ disapproved by the Examiner.
9. ☐ Note the attached Information Disclosure Statement(s) (PTO-1449) Paper No(s). _____
10. ☒ Other: see additional comments, with respect to IDS.

Aristotelis M Psitos
Primary Examiner
Art Unit: 2653



Continuation of 5. does NOT place the application in condition for allowance because: Applicants' arguments focus on the servo system found in the reference to Saga. Saga was not relied upon for such. See the discussion with respect to the acknowledged prior art & either Cheung or the IBM tech. bulletin article as elaborated upon in paragraph 2 (as applied to claims 1 & 3). The reliance upon Saga is as stated in the FR, for the teaching of a combined optical & mag. recording head and a mag. reproducing head arrangement. The ability of having two separate positioners is considered present/taught by the Yanagawa et al document - note col. 2, line 52 to col. 4 line 3. The remaining arguments against the claims all rely upon this issue and hence are also not considered allowable over the art of record. The examiner maintains the final rejection for the reason(s) of record and as amplified above.

with respect to the submitted IDS - it is noted that there is no english translation of the JP search report and no review of such is made. Furthermore, the document 2001-176004 is NOT PRIOR ART and hence not considered. The remaining documents have been reviewed as discued in their abstracts. It is noted that the JP document to Takeshi et al (11-213420) also teaches the mag. reproducing head ability and the combined optical and magnetic recording head as recited in the remaining claims, which the examiner equates as being equivalent to the Saga reference and for what it is relied upon.

Because of the above position, and applicants' desire for a personal interview, (phone messages were left on the examiner's answering machine requesting status and interview in order to discuss the amendment after final of 12/17/03, however due to sheduling conflicts no such interview could be arranged prior to mandatory response by the examiner to the AFTER FINAL amendment) a time/date on 1/12/04 at 2:00PM was set for such an interview. If further conflicts arise, please contact the examiner.

	Type	L #	Hits	Search Text	DBs
1	BRS	L1	183448	mo magneto\$6	USPAT
2	BRS	L2	7	1 and ((magnetic near4 layer) same (management near5 data))	USPAT
3	BRS	L3	23	1 and ((magnetic near4 layer) same (servo near5 data))	USPAT
4	BRS	L4	230248	mo magneto\$6	US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB
5	BRS	L5	21	4 and ((magnetic near4 layer) same (servo near5 data))	US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB
6	BRS	L6	31	((magneto near4 optic\$3) same ((magnetic near4 layer) same servo))	USPAT
7	BRS	L7	27	((magneto near4 optic\$3) same ((magnetic near4 layer) same servo))	US-P GPUB ; EPO; JPO; DERW ENT; IBM_ TDB

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information surface thereon, and a first sputtering apparatus for forming a semi-transparent film on the first information surface of the first substrate;

a second production block comprising a second molding machine for forming a second substrate including a second information surface thereon, and a second sputtering apparatus for forming a reflective film on the second information surface of the second substrate;

a third production block for opposing the semi-transparent film on the first substrate and the reflective film on the second substrate with each other with a photopolymer resin film therebetween then irradiating the photopolymer resin film with light at least through the first substrate and the semi-transparent film, part of the irradiated light undergoing a multiple reflection between the first reflective film and the second reflective film to reduce the time required to cure the photopolymer resin film; and

a transporter for moving the first substrate from the first production block to the third production block and moving the second substrate from the second production block to the third production block, respectively.

19. A method for producing an optical information medium, comprising the steps of:

forming a first substrate having a first information surface on one side thereof;

forming a first reflective film on the first information surface of the first substrate;

forming a second substrate having a second information surface on one side thereof;

forming a second reflective film on the second information surface of the second substrate;

superposing the first and the second substrates so that the first and the second reflective films are opposed to each other with a photopolymer resin therebetween; and

irradiating the photopolymer resin with light through at least one of the first reflective film and the second reflective film to cure the photopolymer resin, thereby bonding the first and the second substrates with each other, part of the irradiated light undergoing a multiple reflection between the first reflective film and the second reflective film to reduce the time required to cure the photopolymer resin.

20. An optical information medium comprising:

a first substrate having a first information surface;

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a first film, formed on the first information surface of the first substrate, for reflecting at least a part of light incident thereon;

a second substrate having a second information surface;

a second film, formed on the second information surface of the second substrate, for reflecting at least a part of light incident thereon; and

a photopolymer resin film provided between the first film and the second film for bonding the first substrate and the second substrate with each other,

wherein at least one of the first film and the second film is semi-transparent, wherein the photopolymer resin film is cured by irradiation of light which is transmitted through at least one of the at least one semi-transparent film, part of the irradiated light undergoing a multiple reflection between the first film and the second film to reduce the time required to cure the photopolymer resin film.

21. A method for producing an optical information medium, comprising the steps of:

forming a first substrate having a first information surface on one side thereof;

forming a first semi-transparent reflection film on the first information surface of the first substrate;

forming a second substrate having a second information surface on one side thereof;

forming a second reflection film on the second information surface of the second substrate;

superposing the first and the second substrates so that the first semi-transparent reflection film and the second reflection film are opposed to each other with a photopolymer resin therebetween; and

irradiating the photopolymer resin with light at least through the first substrate and the first semi-transparent reflection film to cure the photopolymer resin, wherein the photopolymer resin is cured by irradiation of light which is transmitted through the semi-transparent reflection film, part of the irradiated light undergoing a multiple reflection between the first reflection film and the second reflection film to reduce the time required to cure the photopolymer resin, thereby bonding the first and the second substrates with each other.

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